

**Search Notes**

Application No.

10/050,471

Examiner

D. Rutledge

**Applicant(s)**

TABERY ET AL.

Art Unit

2851

**SEARCHED**

Class	Subclass	Date	Examiner
396	569,578, 604	2/17/2004	DR
396	611, 627	2/17/2004	DR
118	52,319	2/17/2004	DR
118	319, 320	2/17/2004	DR
430	30, 311	2/17/2004	DR
427	240	2/17/2004	DR

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
wafer, substrate, coat\$3, develop\$4, process\$3, light, reflectometry, scatterometry, grat\$3, division, partition\$3, sens\$3	2/17/2004	DR
cd, critical, dimension, endpoint, breakpoint, break adj point, control\$4, regulat\$3, modify\$3, chang\$3, adjust\$4, modificatio	2/17/2004	DR
status, progress, feed adj forward, monitor\$3	2/17/2004	DR

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner
396	569, 578	2/17/2004	DR
396	604, 611	2/17/2004	DR
396	627	2/17/2004	DR
430	30, 311		
427	240		
118	52, 319-321	2/17/2004	DR